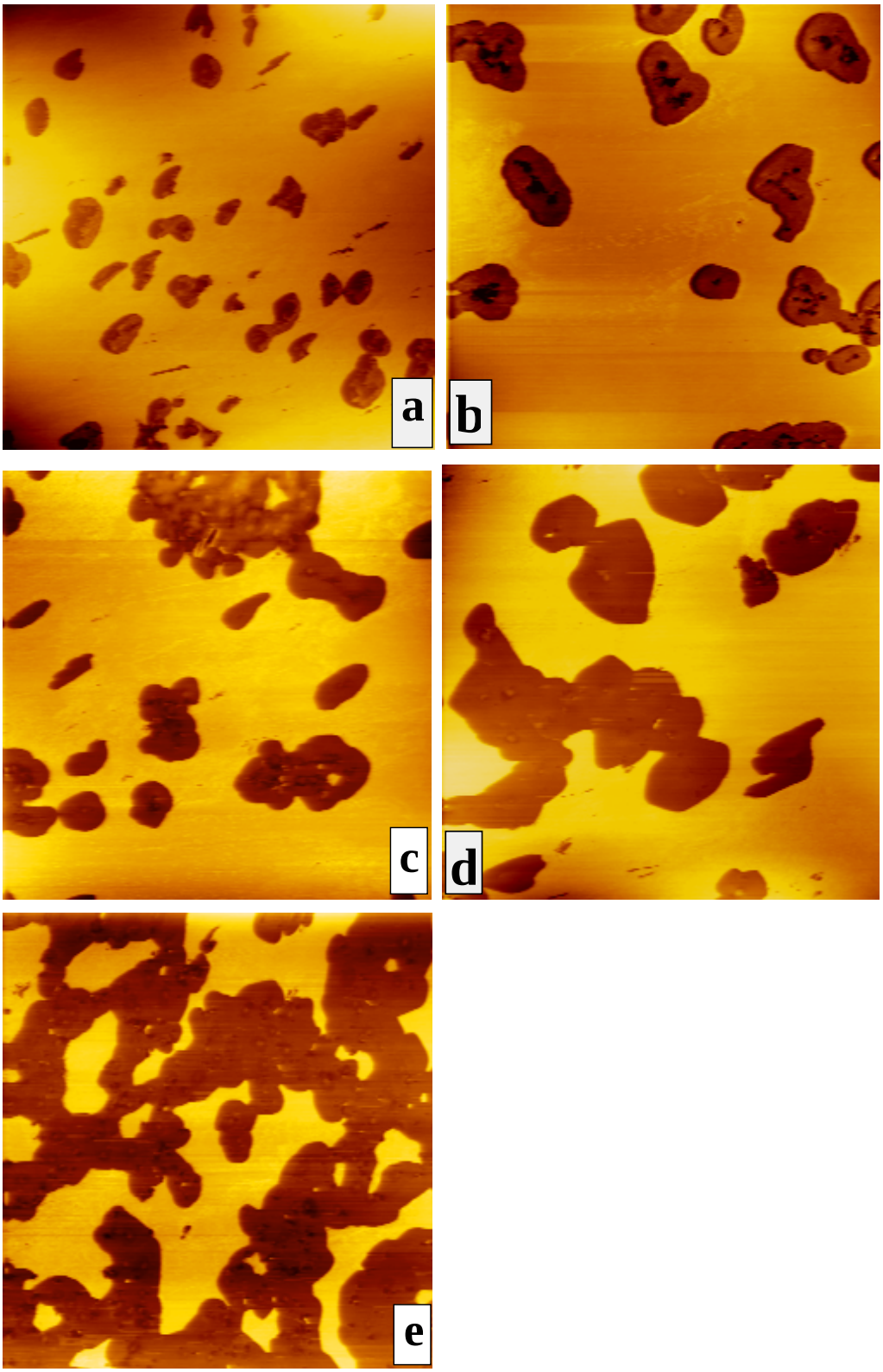

Figure S1 AFM height images of annealed $E_{155}B_{76}$ thin film on silicon. Annealing was performed at 35°C for (a) 5 h, (b) 10 h, (c) 15 h, (d) 20 h and (e) 25 h. Image size is 20×20 μm^2. The bright zones are polymer on the upper layer and the dark zones are

holes in the upper layer and polymers in the bottom layer contacting silicon surface.

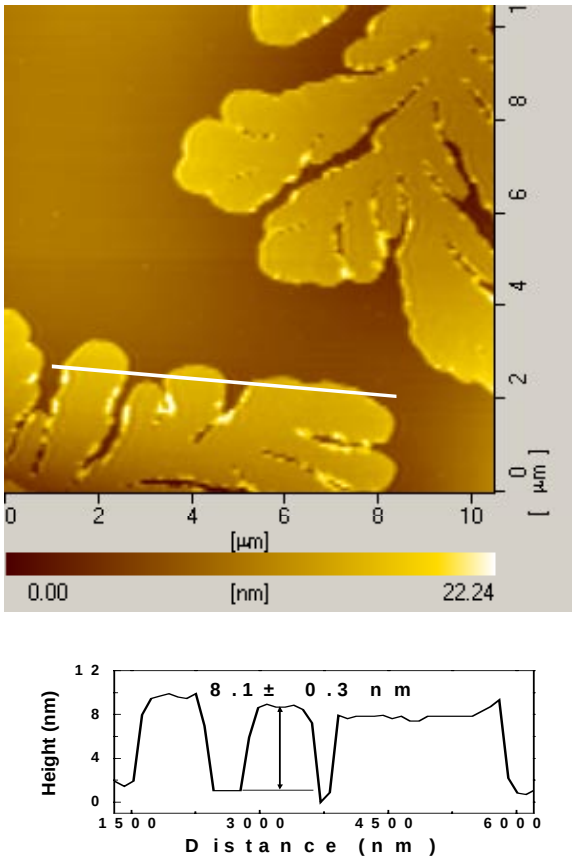

Figure S2 AFM height image of annealed half-layered $E_{76}B_{38}$ thin film on mica.

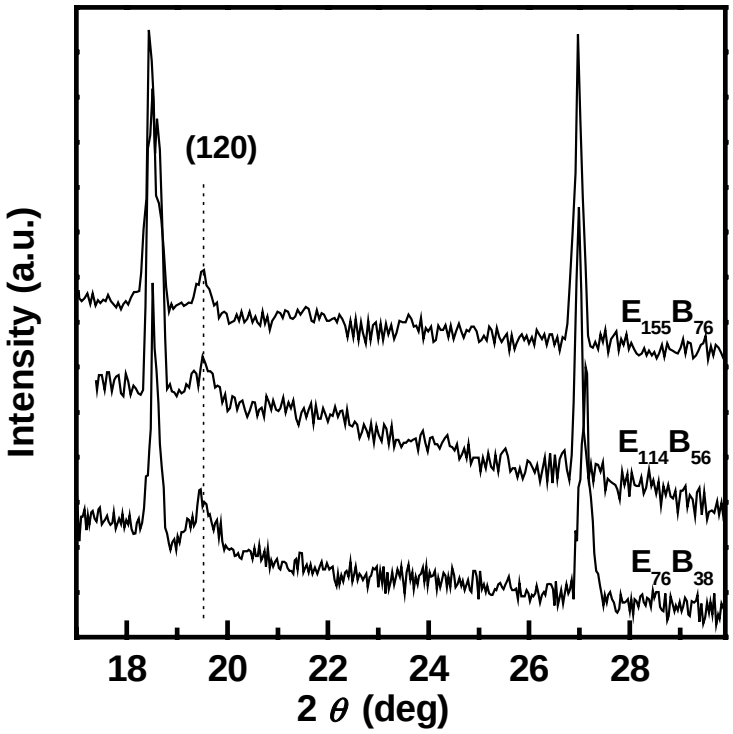

Figure S2 GIXRD patterns of half-layered E_mB_n thin films on mica at an incidence angle of 0.2 °.